

PlasmaTherm 790 PECVD, for SiO₂ and SiN_x Deposition

Operating Instructions

- Load Sample
1. Vent chamber by selecting:
Utilities
Vent
(select at top left of screen)
 2. After chamber vented, place sample at approximate center of platen.
 3. Evacuate chamber by selecting:
Utilities
Pump Chamber (LoVac)
(select at top left of screen, press chamber top down hard)
- Load Process
4. Select
Process
Load
(select at top center of screen)
 5. Double click on desired process. Standard processes are located in the "Standard" folder. If you generate a custom process, please save it in the "Custom" folder.
Loaded process is indicated in process window at lower right of screen.
 6. After process loaded, click **Exit** button at bottom right of window
- Run Process
7. Click **Run** button at bottom of screen
Process runs automatically
- Remove Sample
8. After process finishes, vent chamber and remove sample by selecting:
Utilities
Vent
(select at top of screen)
- Evacuate Chamber
9. After removing sample, evacuate chamber by selecting:
Utilities
Pump Chamber (LoVac)
(select at top of screen, hold top down hard)
 10. After chamber reaches 20 mTorr, double click on:
Utilities
Close Gates (select at top of screen)

ALWAYS LEAVE CHAMBER WITH GATE VALVE CLOSED